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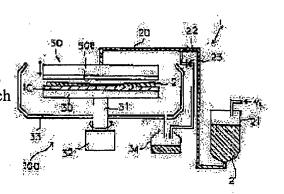
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## (54) COATING FLUID SUPPLY APPARATUS FOR SPIN COATING APPARATUS

(57) Abstract:

PROBLEM TO BE SOLVED: To provide a fluid supply apparatus for a spin coating equipment which has excellent uniformity of a coating thickness on a substrate and a limits coating liquid consumption to minimum by a spin coating method, in which a photoresist and the like are coated in manufacturing a color filter for liquid crystal display and the like.

SOLUTION: A slot-extruded coating liquid supply apparatus 1, which discharges curtain-like coating onto a substrate which is spinning slowly, comprises a slotted coating liquid supply head 50 which allows discharge of the coating liquid 2 to continuously increase from the center to the periphery of the substrate 10, a slit width of the head 50 is continuously enlarged from the center to both sides and a slit distance between a manifold provided inside the head 50 and an end 50e of the head is reduced from the center to both ends.



## **LEGAL STATUS**

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